



**PATENT APPLICATION**

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Hiroki YOSHIKAWA et al.

Group Art Unit: 1756

Application No.: 10/806,202

Examiner: S. ROSASCO

Filed: March 23, 2004

Docket No.: 119162

For: METHOD OF PRODUCING PHASE SHIFT MASK BLANK, METHOD OF PRODUCING PHASE SHIFT MASK, PHASE SHIFT MASK BLANK, AND PHASE SHIFT MASK

**REQUEST FOR RECONSIDERATION**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

In reply to the March 27, 2007 Office Action, reconsideration of the rejection is respectfully requested in light of the following remarks.

Claims 1, 3, 5, and 7-34 are pending in this application. The Office Action rejects claims 1, 3, 5, 7-12 and 25-34 under 35 U.S.C. §103(a) as unpatentable over Isao in view of Angelopoulos, Miyamura and Mitsui. Applicants respectfully traverse the rejection.

**I. Rejection Under 35 U.S.C. §103(a)**

The Office Action rejects claims 1, 3, 5, 7-12 and 25-34 under 35 U.S.C. §103(a) as unpatentable over Isao in view of Angelopoulos, Miyamura and Mitsui. Applicants respectfully traverse the rejection.

Applicants respectfully note that the Office Action mischaracterizes the claimed invention at page 4 as being directed to a method including "at least a step of forming *one or more* phase shift films on a substrate." Applicant's amendments made on March 5, 2007, clearly negate this mischaracterization of the instant invention. That Amendment amended claim 1 to recite "two or more" films. Accordingly, by applying the mischaracterization of